Abstract

Drying apparatus for a semiconductor wafer

The invention relates to a drying apparatus which is designed, during at least one drying process, to dry at least one wetted semiconductor wafer (200) arranged temporarily therein on a holder unit (10), wherein the drying apparatus (100) comprises a dryer cover unit (110). The dryer cover unit (110) comprises at least one transparent pane element (111, 112, 113), which is designed for the purpose and arranged on the dryer cover unit (110) in such a way that, in a closed state of the dryer cover unit (110), it provides a substantially unrestricted optical view of substantially the entire surface of the arranged semiconductor wafer (200), in particular for at least one operator, from outside the drying apparatus (100) via the at least one transparent pane element (111, 112, 113) when considered over the entire at least one drying process.

Figure for the abstract: Figure 1